

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Chih-Chien LIU, et al

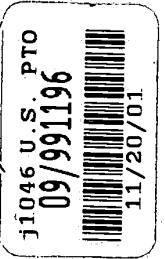
Serial No. Unassigned

Filed: November 20, 2001

For: HIGH DENSITY PLASMA  
CHEMICAL VAPOR DEPOSITION  
PROCESS

Examiner: Unassigned

Art Unit: Unassigned



INFORMATION DISCLOSURE STATEMENT

Assistant Commissioner for Patents  
2900 Crystal Drive  
Arlington, VA 22202-3513

Dear Sir:


Pursuant to 37 C.F.R. § 1.97, the Examiner may wish to consider the references listed on the attached PTO Form 1449. In submitting these references, no representation is made or implied that the references are or are not material to the examination of this application.

The references were cited in U.S. Patent Application Serial No. 09/546,174, which is a continuation of U.S. Application Serial No. 08/958,460, now U.S. Patent No. 6,117,345, from which priority under 35 U.S.C. § 120 was claimed. Copies of these references are enclosed herewith.

This IDS is filed along with the application. Accordingly, no fee is believed due. However, any fee associated herewith may be charged to Deposit Account No. 50-1123.

Respectfully submitted,

November 20, 2001

  
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